Title of Invention: SUBSTRATE PROCESSING DEVICE, POLISHING DEVICE, AND SUBSTRATE PROCESSING METHOD

ABSTRACT

Provided are a substrate processing device, a polishing device, and a substrate processing method to suppress condensation in an exhaust duct of a substrate processing device for processing a substrate with a liquid. The substrate processing device includes a processing module for processing the substrate with a liquid, and a gas-liquid separation tank connected to the exhaust outlet of the processing module, which separates the liquid from the exhaust received from the processing module and releases the exhaust into an exhaust duct. The gas-liquid separation tank includes a tank body, a heat exchanger arranged inside the tank body and cools the exhaust, and an air nozzle arranged inside the tank body and supplies air to cool the exhaust.

FIG. 3